Optocoupler study :

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9th ESA / ESTEC D/TEC QCA Final Presentation Day 2009. January 27th & 28th 2009. PSI-CH 5232 Villigen Switzerland

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Acknowledgments

- This work has been done under ESA contract n° 19623/05/NL/PA; we address a very warm thanks to Reno Harboe Sorensen for his continuous support and exciting discussions.
- We would also like to particularly acknowledge Marcus H. MendenHall and Robert A. Weller from Vanderbilt University, to have provided the GEANT4 module of the modified coulombic scattering model taking into account the screening effects (ZBL) described in references below:

[Weller-2004] Robert A. Weller, Marcus H. MendenHall, Daniel M. Fleetwood, "A Screened Coulomb scattering Module for Displacement Damage computations in GEANT4", IEEE Trans. Nucl. Sci, 51, n°6, pp 3669-3677, (2004).

[Mend-2006] Marcus H. MendenHall, Robert A. Weller, "An algorithm for computing Screened Coulomb scattering in GEANT4", Nuclear Instruments and Methods B, 2006.



- The objective is to define a procedure for part selection and assessment regard TID and TNID cumulative constraints.
- Three part types were procured : diodes and transistors can be irradiated <u>separately</u>.

Part name	Al _x Ga _{1-x} As diode Stoechiometry	
4N49 (880 nm) / ISOLINK	x=0.02	
OLH249 (830 nm) / ISOLINK	x=0.11	3 different technologies
66099 (660 nm) / MICROPAC	x=0.35	
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3 different proton energies:

60 MeV	
100 MeV	
200 MeV	



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- Measured parameters: Measurements versus:
 - CTR_{opto}
 - CTR_{diode}
 - CTR_{transistor}
 - Diode's τ_{RR0}

- Fluence
- NIEL from tables or calculated with GEANT4

Several NIEL tables exist on pure AsGa



• NIEL was calculated with GEANT4 on Al_xGa_(1-x)As material with the modified module for coulombic scattering => within 10% shift between x=0 and x=0.35

Ep (MeV)	NIEDR (MeV.cm²/g)	Si (ρ = 2,33)	AsGa (ρ = 5,32)	Al _x Ga _{1-x} As x=2% ($\rho = 5,31$)	$Al_{x}Ga_{1-x}As = 11 \%$ ($\rho = 5,26$)	Al _x Ga _{1-x} As x=35% ($\rho = 5,13$)
60	Elastic (Coulombic)	1,744.10 ⁻³	1,204.10-3	1,213.10-3	1,213.10-3	1,201.10 ⁻³
	Inelastic (Nuclear)	5,88.10 ⁻⁴	7,39.10-4	8,25.10-4	7,99.10-4	6 , 61.10 ⁻⁴
100	Elastic (Coulombic)	1,104.10 ⁻³	7,76.10-4	7,64.10-4	8,17.10-4	7 , 57.10 ⁻⁴
	Inelastic (Nuclear)	5,83.10 ⁻⁴	8,48.10-4	7,24.10-4	7,54.10-4	6 , 10.10 ⁻⁴
200	Elastic (Coulombic)	5,70.10-4	4,32.10-4	4,19.10-4	4,00.10-4	3,93.10-4
	Inelastic (Nuclear)	4 , 99.10 ⁻⁴	7,76.10-4	6,51.10-4	6,06.10-4	6,97.10 ⁻⁴



 Comparison between Barry's value and Calculation with GEANT4, using modified module (Mend-2006)

		Silio	Silicon		Ga	Hypothesis of 10µm
Ep (MeV)	$\frac{\text{NIEDR}}{(\text{MeV.cm}^2/\text{g})}$	GEANT4	Barry	GEANT4	Barry	target thickness
(0)	Elastic (Coulombic)	1,744.10 ⁻³	3, 36.10 ⁻³	1,204.10-3	1,60.10 ⁻³	
60 -	Inelastic (Nuclear)	5,88.10-4	-	7,39.10-4	-	
100	Elastic (Coulombic)	1,104.10 ⁻³	2, 60.10 ⁻³	7 , 76.10 ⁻⁴	1 , 25.10 ⁻³	Some discremancy
	Inelastic (Nuclear)	5,83 .10 ⁻⁴	-	8,48.10-4	-	between Barry's table
200	Elastic (Coulombic)	5,70.10-4	2,02 .10 ⁻³	4,32.10-4	8,5.10-4	and GEANT4 results
	Inelastic (Nuclear)	4, 99.10 ⁻⁴	-	7,76.10-4	-	



- Parts were procured with diodes and transistors as separate elements.
- The experimental set-up allows to separate the contribution of the irradiated diodes and transistors in the overall degradation, thanks to the measurements done with un-irradiated reference parts.
- All the measurements are remote controlled for higher efficiency.



During the irradiation, diode and transistors are coupled





Set-up with detailed view of two coupled branches



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Experimental set-up presentation (VIDEO)

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CTR versus fluence : 4N49



•		60 MeV
0	Δ	100 MeV
•		200 MeV



Transistor degradation measured with reference diode

- The diode is the main contributor to the overall degradation
- The degradation at 200 MeV seems > at 100 MeV > 60 MeV





CTR versus fluence : OLH249



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- The transistor is the main contributor to the overall degradation
- The degradation at 200 MeV seems > at 100 MeV > 60 MeV



CTR versus fluence : 66099



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Transistor degradation measured with reference diode



- The diode is the main contributor to the overall degradation
- The degradation at 200 MeV <u>seems</u> ~ at 100 MeV ~ 60 MeV



CTR versus NIEL: which NIEL to use?



- As in [4], a target thickness of 10 µm was considered for the elastic NIEL calculation with GEANT4
- In GEANT4, the MultiScattering module was skipped and replaced by the module given by M.H.MendenHall et R.A. Weller [4].

[4] R.A. Weller et al., "A screened scattering Coulomb module for displacement damage computations in GEANT4", IEEE Tr. on Nuclear Science, vol.51, no.6, December 2004

- [1] L. Barry, A. J. Houdayer, P. F. Hinrichsen, W. G., Letourneau and J. Vincent,
- "The Energy Dependence of Lifetime Damage Constants in GaAs LEDs for 1-500 MeV Protons, "IEEE Trans. Nucl. Sci., 42, 2104 (1995)





Transistor degradation measured with reference diode



- The diode is the main contributor to the overall degradation
- The degradation at 200 MeV is > at 100 MeV > 60 MeV



Experimental results vs. Elastic NIEL

CTR versus NIEL (GEANT4): OLH249



Transistor degradation measured with reference diode



 The transistor is the main contributor to the overall degradation

The degradation at 200 MeV is > at 100 MeV >~ 60 MeV





Transistor degradation measured with reference diode



The diode is the main contributor to the overall degradation

The degradation at 200 MeV is > ~ at 100 MeV ~ 60 MeV



Experimental results vs. (Elastic+Inelastic) NIEL • CTR versus NIEL (GEANT4): 4N49



Transistor degradation measured with reference diode



4N49 IF=1mA rel.CTR T

- The diode is the main contributor to the overall degradation
 - The degradations are comparable at all energies



Experimental results vs. (Elastic+Inelastic) NIEL CTR versus NIEL (GEANT4): OLH249





OLH249 IF=1mA rel.CTR T

Transistor degradation measured with reference diode

- The transistor is the main contributor to the overall degradation
- The degradations are ~greater at 200 MeV than the other energies



Experimental results vs (Elastic+Inelastic) NIEL CTR versus NIEL (GEANT4): 66099



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Transistor degradation measured with reference diode



66099 IF=1mA rel.CTR T

- The diode is the main contributor to the overall degradation
- The degradations are comparable at all energies



Experimental results Preliminary conclusion

Relative CTR degradations are :

- Greater at 200 MeV than at the other energies if the considered NIEL is based on Barry's table (results not shown here) or elastic contribution
- Comparable within [60MeV-200 MeV] range if the (elastic + inelastic) contributions are considered.



• Effect of NIEL on $\tau_{RR:}$



In the following, τ_{RR} is measured at IR=-4 mA



• Effect of NIEL on τ_{RR} : Correlation between diode's absolute CTR degradation and its τ_{RR} degradation

5.0E-02 pre-irradiation 4.5E-02 ۹ 💑 4.0E-02 3.5E-02 Фр1 3.0E-02 2.5E-02 2.0E-02 Фр2 1.5E-02 Фр3 Δ 1.0E-02 5.0E-03 0.0E+00 0 100 200 300 400 500 600 TRR at IR= -4mA [ns]

4N49 IF= 1mA abs.CTR(diode) vs TRR IR= -4mA

• Considering the pre and post irradiation values, the absolute diode's CTR is not depending on the τ_{RR} .



• Effect of τ_{RR0} on the relative diode's CTR degradation Let's define $\Delta rel.CTR = (CTR_0-CTR)/CTR_0 = (1 - CTR/CTR_0)$ at one NIEL value





• Effect of τ_{RR0} on the relative diode's CTR degradation



• This function can be fitted according to $CTR/CTR_0 = (\tau_{RR}/\tau_{RR0})^N$, and N integer greater than 1 ^{[2], [3]}

[2] A. L. Barry, A. J. Houdayer, P. F. Hinrichsen, W. G., Letourneau and J. Vincent, "The Energy Dependence of Lifetime Damage Constants in GaAs LEDs for 1-500 MeV Protons," IEEE Trans. Nucl. Sci., 42, 2104 (1995)
 [3] A.J. Houdayer et al., GaAs LED based NIEL spectrometer fort he space radiation environment, IEEE Tr. on Nuclear Science, vol.47, no.3, June 2000.



- Effect of τ_{RR0} on the relative diode's CTR degradation
- CTR/CTR₀= $(\tau_{RR}/\tau_{RR0})^{N.}$ [1] Since $\Delta(1/\tau_{RR}) = K_{\phi} \cdot \Phi = K_{NIEL}$. NIEL, [2]

$$\Rightarrow \Delta rel.CTR = (1 - CTR/CTR_0)$$

= 1- $(\tau_{RR0}/\tau_{RR})^{-N}$

= 1- $(1+\tau_{RR0}, K_{\phi}, \Phi)^{-N}$ [3]

= 1- (1+ τ_{RR0} . K_{NIEL}. NIEL)^{-N} [4]

=> According to this expression, one can expect Δrel.CTR increase with τ_{RR0} increase. Calculation can be performed to obtain K₀ or K_{NIEL} and N.

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calculation of N on 4N49:



Calculation of K_{NIEL} (GEANT 4 Elastic) on 4N49:



• (1 - CTR/CTR₀) at a NIEL of 8.10⁶ MeV.g-1 (GEANT4 ELASTIC) with respect to τ_{RR0} (4N49 points)

IF= 1mA DELTA rel.CTR(diode) est. at NIEL AsGa GEANT4 [MeV.g-1]=



Experimental results : relative diode degradation • Δrel.CTR (diode) = (1 - CTR/CTR₀), NIEL = 8.10⁶ MeV/g @ If = 1mA





Experimental results : relative diode degradation • Δrel.CTR (diode) = (1 - CTR/CTR₀), NIEL = 8.10⁶ MeV/g @ If = 10 mA





Experimental results : relative diode degradation Δrel.CTR (diode) = (1 - CTR/CTR₀), NIEL = 4,9.10⁷ MeV/g If = 1mA





Experimental results : relative diode degradation

Δrel.CTR (diode) = (1 - CTR/CTR₀), NIEL = 4,9.10⁷ MeV/g @ If = 10 mA





Experimental results : relative optocoupler degradation @ If= 1 mA & NIEL= 4,9.10⁷ MeV/g



 Discrepancy for OLH249 : remember, the main contribution to degradation is coming from transistor

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Experimental results : relative optocoupler degradation @ If= 10 mA & NIEL= 4,9.10⁷ MeV/g



 Discrepancy for OLH249 : remember, the main contribution to degradation is coming from transistor

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Experimental results : relative optocoupler degradation @ If= 1 mA & NIEL= 4,9.10⁷ MeV/g



Experimental results : relative optocoupler degradation @ If= 10 mA & NIEL= 4,9.10⁷ MeV/g





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Experimental results : relative optocoupler degradation @ If= 1 mA & NIEL= 4,9.10⁷ MeV/g





Experimental results : relative optocoupler degradation @ If= 10 mA & NIEL= 4,9.10⁷ MeV/g





- NIEL calculation performed with GEANT4 (elastic) and (elastic + inelastic) on AsGa thickness of 10µm
- Degradation vs. NIEL curves fit very well within [60-200 MeV] range under the assumption of total NIEL.
 - Optocoupler testing can be performed with a single energy with confidence in results representativeness
 - To investigate the possibility to extend it to other optoelectronic devices
- If only elastic contribution is considered, then the curve at 200 MeV show some higher degradation as compared with the 60 and 100 MeV. Some contribution coming from material surrounding the active layer is suspected.
- The lower the τ_{RR0} the lower the degradation



- Equations [1] to [4] used for 4N49, allowed to predict the degradation of other diodes corresponding to other technologies vs. NIEL, after K_{NIEL}(4N49) and N(4N49) parameters obtained by non-linear regression.
- The diode degradation is only depending on $\tau_{\rm RR0}$ not on its technology.
- Part selection based on diode $\tau_{\rm RR0}$ and transistor $\tau_{\rm RR0}$ measurement seems a relevant criteria for optocoupler assessment regarding TNID : the lower $\tau_{\rm RR0}$ would lead to the lower degradation for both transistor and diode.



- Work on going:
 - Verify that lower transistor τ_{RR0} would lead to lower optocoupler degradation
 - Verify that equations [1] to [4] applied to TID with K_{TID}(4N49) and N(4N49) regression allow to predict diode / optocouplers TID degradation.



This study could be performed after:

- More than 21000 measurements,
- 15 pizzas great size,
- 5 kg cakes,
- Ikg peanuts...
- 12 L Beers (not for me)
- 20 L banana juices (for me) also...

